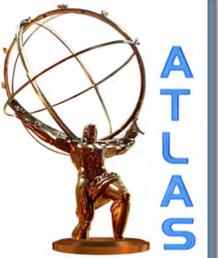




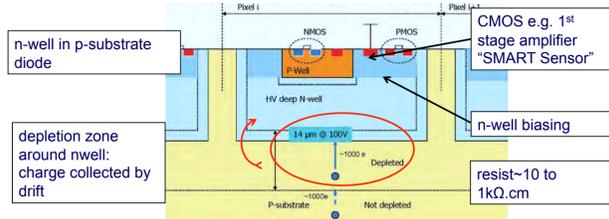
# Development of radiation hard CMOS Active Pixel Sensors for HL-LHC

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## Develop depleted radiation hard CMOS Sensors for ATLAS ITK

- ATLAS ITK upgrade for Phase II Pixel detector requires radiation hard sensors, which present CMOS MAPS cannot do (not radiation hard & too slow)
- Started RD to develop commercial CMOS processes to radiation hard sensors through optimized designs, high voltage processes (>100V on chip) and higher resistivity (100Ohm\*cm to kOhm\*cm)



### Monolithic solutions benefits:

- Thin & light detector modules
- Simplified assembly and cost advantage for large areas

### Hybrid solution benefits

- Fast and complex readout in separate digital chip to cope with highest hit rates at smallest radii
- CMOS sensor + analog stages

## XFAB SOI 180 nm prototype XTB01 & XTB02

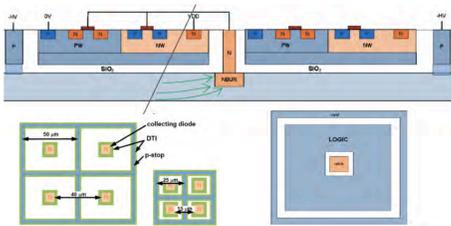
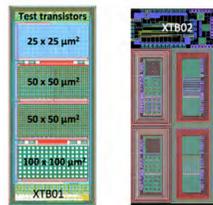
- Monolithic test chip to investigate transistor and sensor charge collection performance
- Electronics isolated from substrate through oxide (BOX)
- Small collection well (capacitance!) but no competing wells
- Isolating deep P well between CMOS and BOX to avoid back-gate effect

XTB01: 4 different pixel matrices with 3T readout and transistor test structures

XTB02: Passive diodes to study charge collection; includes deep p-spray and p-stop structures to intercept accumulation layer

### XFAB Trench SOI 0.18 μm CMOS low-power 1.8/5.0V

- P-type bulk, 4 metal layers,
- Prototype size Size: 5 x 2 mm<sup>2</sup>
- Wafer size: 8" with high handling wafer resistivity:
  - 100 Ω cm CZ
  - 1 kΩ cm possible
- HV applied from front side up to 300V



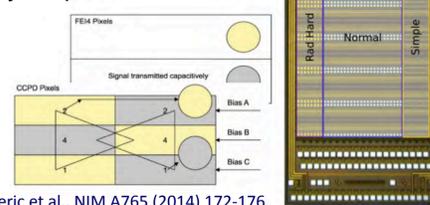
Hemperek, Kishishita, Krüger, NW arxiv 1412.3973, accepted NIM A

## AMS H18 180nm HV2FEI4 Version 2 & 4

- Matched to ATLAS FEI4 readout chip (50x250μm pixel size) and includes sub-pixel encoding
- Sub-pixel (size 33x125μm) includes Preamp + Shaper + Discriminator

Produced in AMS H18 process:

- ρ=10Ωcm with bias 60–100V
- Depletion depth ~10 μm
- Q (theoretical) ~1000 e<sup>-</sup> by drift
- capacitively coupled to FEI4



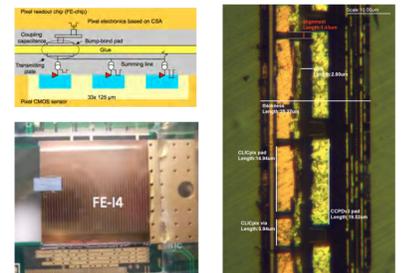
I. Peric et al., NIM A765 (2014) 172-176

### HV2FEI4 CCPD Version 2:

- Three pixel types
- Voltage based sub pixel encoding
- First to work after 850 Mrad

### HV2FEI4 CCPD Version 4:

- Lower noise
- Pulse length or voltage based sub-pixel encoding

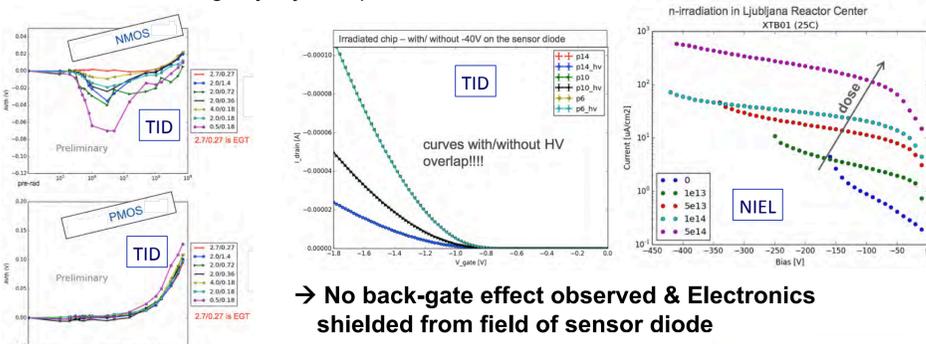


### Capacitive coupling to FEI4

- Capacitive readout AMS CMOS sensor to input of ATLAS FEI4 pixel readout chip
- "Capacitive Coupled Pixel Detector" (CCPD)
- Flip chip on SET FC150
- Achieved glue layer thickness of 3μm
- Alignment of 1-1.5μm
- Also demonstrated planarity and thickness on full size FEI4 assemblies (21x18mm) using planar sensors

## Results on XFAB CMOS prototype

- γ-Irradiated up to 700Mrad, annealed after irradiation
- n-irradiated at Triga/Ljubljana up to 5x10<sup>14</sup> n/cm<sup>2</sup>



→ No back-gate effect observed & Electronics shielded from field of sensor diode

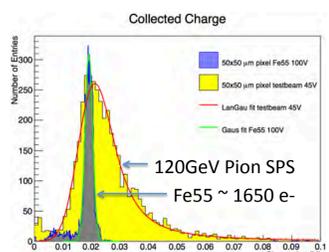
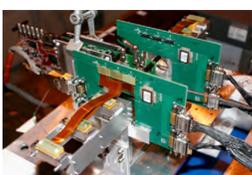
- TID leads to BOX charge-up, which creates an accumulation layer in the substrate between DNW and bias-DPW

- Increased leakage
- Reduced max bias voltage

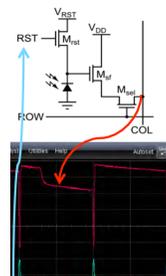
- Implemented p-stop (DPW) to intercept accumulation layer in XTB02

→ DPW (P-Stop) reduces leakage and leads to high breakdown voltage

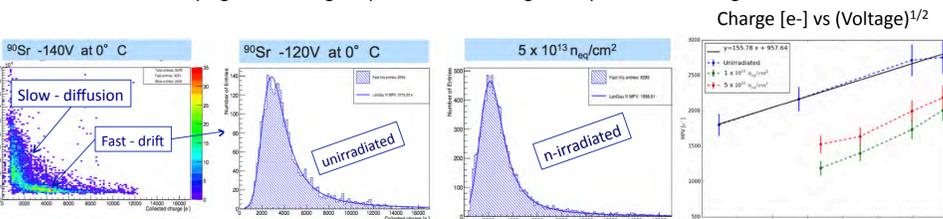
### Signals in Source & Beam tests XFAB XTB01



- XFAB readout with 3T structure
- 50x50 μm pixels



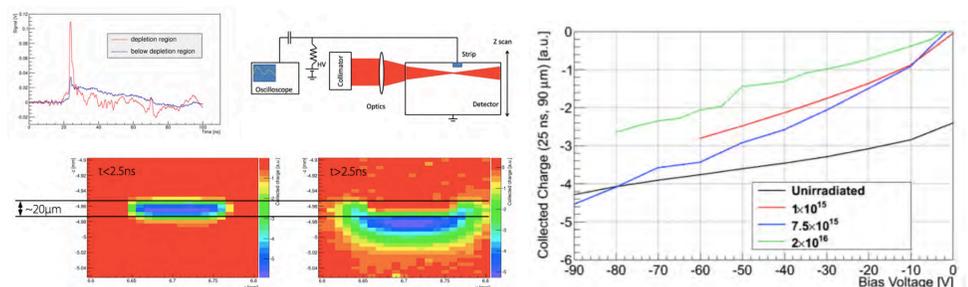
- Observe depletion of ~31μm (calculated ~36μm)
- Observe faster (high field region) and slower signals (lower field regions)



## Results on AMS 180nm CCPD

### Charge Collection Studies

- Lab characterization before and after irradiation: Edge Transient Current Technique



- Drift and diffusion are distinguished by timing cut at 2.5ns
- In-time signal fraction increases with irradiation
- Acceptor removal due to irradiation may lead to increased substrate resistivity & depleted area

### Beam test results on AMS 180nm

- Unirradiated and irradiated HV2FEI4 CCPD Version 4 (neutrons 1x10<sup>15</sup> neq/cm<sup>2</sup>)

### Overall efficiency (time-integrated):

- Unirradiated 99.7% at -12V bias, irradiated 96.2% at -30V
- Signal after irradiation ~ 1500 e<sup>-</sup> (SNR ~25) but in-time efficiency not yet met

